

Applicant : Y. Long He et al.
Serial No. : 10/076,129
Filed : February 13, 2002
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Attorney Docket: 10559-583001 / P12764

REMARKS

Claims 1-14, 16-23, 27-31, and 33-40 are pending in the application. Claims 1, 18, 21, 24, 31, 33, and 35 are independent. The applicants thank the Examiner for allowance of claims 1-14, 16-23, 27-30, and 35-40. Favorable reconsideration and further examination of claims 31, 33, and 34 are respectfully requested.

Below, the applicants' comments are preceded by related remarks of the examiner set forth in small bold font.

3. Claims 31-32 are rejected under 35 USC102(b) as being anticipated by Pu et al. (5,843,847).

Pu et al. discloses a process for rie etching a BPSG layer on a wafer using a patterned photo resist etch mask, and a plasma which is comprised of an inert gas (i.e., -Ar, etc.), a nitrogen compound (i.e., -N₂, etc.), a hydrofluorocarbon (i.e., -CHF₃, etc.), and a fluorocarbon absent (i.e., -CF₄). The etching process is characterized by low micro-loading. This is discussed specifically in columns 2-3; and discussed in general in columns 1-16. This is shown in figures 1-8.

The applicants submit that Pu does not disclose or suggest "providing a substrate comprising a quartz plate, portions of the substrate being covered by a resist," as recited in amended claim 31.

4. Claims 33-34 are rejected under 35 U.S.C. 102(b) as being anticipated by Oda et al. as applied in paragraph 18 of the previous office action.

The applicants submit that Oda does not disclose or suggest "providing a substrate in a chamber, the substrate comprising a quartz plate," as recited in amended claim 33.

Claim 34 is patentable for at least the same reasons as claim 33.

In view of the foregoing amendments and remarks, the entire application is believed to be in condition for allowance, and such action is respectfully requested at the Examiner's earliest convenience.

Applicants' undersigned attorney can be reached at the address shown below.

Telephone calls regarding this application should be directed to the undersigned at 617-956-5959.

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Please apply any charges or credits to deposit account 06-1050, referencing attorney docket 10559-583001.

Respectfully submitted,

Date: Nov. 19, 2003

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** See attached document certifying that Rex Huang has limited recognition to practice before the U.S. Patent and Trademark Office under 37 CFR § 10.9(b).*

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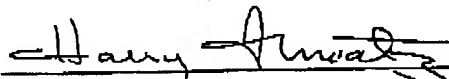
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Expires: May 16, 2004



Harry I. Moatz
Director of Enrollment and Discipline